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COMPARING DEVICE

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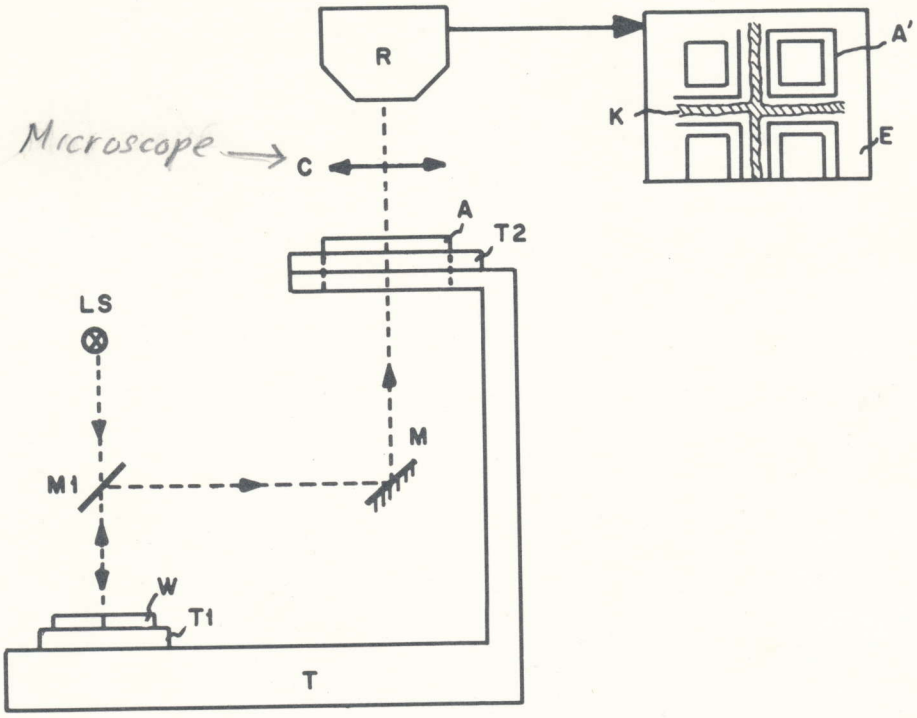

This electro-optical device enables the kerfs appearing on a wafer to be inspected after the wafer dicing operation. This device compares the kerfs to the wafer with a reference mask by superimposing the images of the wafer and the mask.

The light source LS illuminates the wafer W. The image of this wafer is projected on the mask A by the unsilvered mirror M1 and the mirror M. The microscope C receives the superposition of the images of the wafer and of the mask and transmits the result ot a Camera R which controls a television screen E.

The table T is an X-Y table which enables both the wafer and the mask to be positioned with respect to the camera. The relative positioning of the wafer and the mask is obtained by rotational movement of the wafer support T1 by X-Y translation movements of the mask support T2. Comparison of both images is carried out on the television screen E, by comparing the image A' of the mask with the image K of the wafer kerfs.